```
* * * * * * * * * * * * * * * * STN  Columbus  * * * * * * * * * * * * * * * *

FILE 'HOME' ENTERED AT 15:55:01 ON 03 MAR 2010

=> FILE REG
COST IN U.S. DOLLARS                                    SINCE FILE      TOTAL
                                                           ENTRY    SESSION
FULL ESTIMATED COST                                         0.22       0.22

FILE 'REGISTRY' ENTERED AT 15:55:15 ON 03 MAR 2010
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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provided by InfoChem.

STRUCTURE FILE UPDATES:    2 MAR 2010  HIGHEST RN 1207712-05-7
DICTIONARY FILE UPDATES:   2 MAR 2010  HIGHEST RN 1207712-05-7

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH June 26, 2009.

  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and
predicted properties as well as tags indicating availability of
experimental property data in the original document.  For information
on property searching in REGISTRY, refer to:

http://www.cas.org/support/stngen/stndoc/properties.html

=> S TRIAZINE AND ETHENYL AND TRICHLORO
        252714 TRIAZINE
        933785 ETHENYL
        284738 TRICHLORO
L1         246 TRIAZINE AND ETHENYL AND TRICHLORO

=> S L1 AND ETHOXY
       2879810 ETHOXY
L2          12 L1 AND ETHOXY

=> D 12

L2   ANSWER 12 OF 12  REGISTRY  COPYRIGHT 2010 ACS on STN
RN   97802-78-3  REGISTRY
ED   Entered STN:  31 Aug 1985
CN   1,3,5-Triazine, 2-[4-[2-(4-ethoxyphenyl)ethenyl]phenyl]-4,6-
     bis(trichloromethyl)-  (CA INDEX NAME)
MF   C21 H15 C16 N3 O
SR   CA
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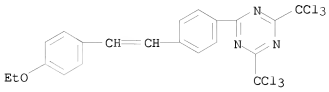
LC STN Files: CA, CAPLUS, USPATFULL



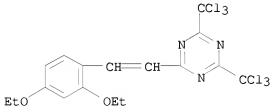
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> S L1 AND DIETHOXY
147438 DIETHOXY
L3 2 L1 AND DIETHOXY

=> D 1-2

L3 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2010 ACS on STN
RN 229326-43-6 REGISTRY
ED Entered STN: 29 Jul 1999
CN 1,3,5-Triazine, 2-[2-(2,4-diethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C17 H15 C16 N3 O2
SR CA
LC STN Files: CA, CAPLUS

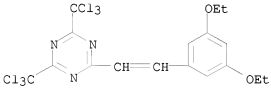


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L3 ANSWER 2 OF 2 REGISTRY COPYRIGHT 2010 ACS on STN
RN 209530-49-4 REGISTRY

ED Entered STN: 06 Aug 1998
CN 1,3,5-Triazine, 2-[2-(3,5-diethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C17 H15 Cl6 N3 O2
SR CA
LC STN Files: CA, CAPLUS



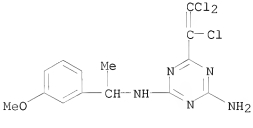
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> S L1 AND DI AND OXY
25835905 DI
16245265 OXY
L4 24 L1 AND DI AND OXY

=> D 1-24

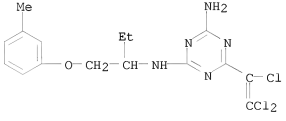
L4 ANSWER 1 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 1138830-85-9 REGISTRY
ED Entered STN: 26 Apr 2009
CN 1,3,5-Triazine-2,4-diamine, N2-[1-(3-methoxyphenyl)ethyl]-6-(1,2,2-trichloroethenyl)- (CA INDEX NAME)
MF C14 H14 Cl3 N5 O
SR CA
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

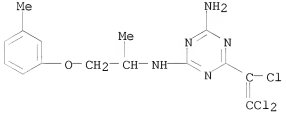
L4 ANSWER 2 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 1138830-67-7 REGISTRY
ED Entered STN: 26 Apr 2009
CN 1,3,5-Triazine-2,4-diamine, N2-[1-[(3-methylphenoxy)methyl]propyl]-6-(1,2,2-trichloroethenyl)- (CA INDEX NAME)
MF C16 H18 Cl3 N5 O
SR CA
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 3 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 1138830-57-5 REGISTRY
ED Entered STN: 26 Apr 2009
CN 1,3,5-Triazine-2,4-diamine, N2-[1-methyl-2-(3-methylphenoxy)ethyl]-6-(1,2,2-trichloroethenyl)- (CA INDEX NAME)
MF C15 H16 Cl3 N5 O
SR CA
LC STN Files: CA, CAPLUS



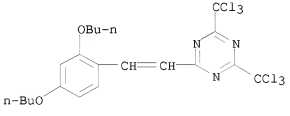
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 4 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 504396-10-5 REGISTRY *
* Use of this CAS Registry Number alone as a search term in other STN files may
result in incomplete search results. For additional information, enter HELP RN* at an online arrow prompt (=>).
ED Entered STN: 24 Apr 2003
CN 2,7-Naphthalenedisulfonic acid,
5-amino-3-[[4-(ethenylsulfonyl)phenyl]azo]-4-hydroxy-, disodium salt, reaction products with
7-amino-4-hydroxy-3-[(4-methoxy-2-sulfophenyl)azo]-
2-naphthalenesulfonic acid disodium salt, propylenediamine,
2,4,6-trichloro-1,3,5-triazine and 2,4,6-trifluoro-1,3,5-triazine
(CA INDEX NAME)
MF Unspecified
CI MAN, GRS
SR CAS Client Services
LC STN Files: CHEMLIST

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

L4 ANSWER 5 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 229326-45-8 REGISTRY
ED Entered STN: 29 Jul 1999
CN 1,3,5-Triazine, 2-[2-(2,4-dibutoxyphenyl)ethenyl]-4,6-
bis(trichloromethyl)- (CA INDEX NAME)
MF C21 H23 C16 N3 O2
SR CA
LC STN Files: CA, CAPLUS

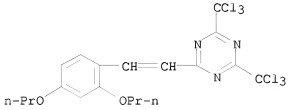


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 6 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 229326-44-7 REGISTRY

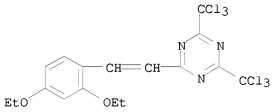
ED Entered STN: 29 Jul 1999
CN 1,3,5-Triazine, 2-[2-(2,4-dipropoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C19 H19 Cl6 N3 O2
SR CA
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 7 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 229326-43-6 REGISTRY
ED Entered STN: 29 Jul 1999
CN 1,3,5-Triazine, 2-[2-(2,4-diethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C17 H15 Cl6 N3 O2
SR CA
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

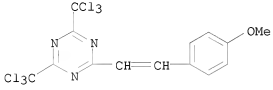
1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 8 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 212955-92-5 REGISTRY

ED Entered STN: 21 Oct 1998
CN Benzenediazonium, 4-(phenylamino)-, sulfate (2:1), polymer with formaldehyde and 2-[2-(4-methoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)-1,3,5-triazine (9CI) (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 1,3,5-Triazine, 2-[2-(4-methoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)-, polymer with formaldehyde and (4-phenylamino)benzenediazonium sulfate (2:1) (9CI)
CN Formaldehyde, polymer with 2-[2-(4-methoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)-1,3,5-triazine and 4-(phenylamino)benzenediazonium sulfate (2:1) (9CI)
MF (C14 H9 C16 N3 O . C12 H10 N3 . C H2 O . 1/2 O4 S)x
CI PMS
PCT Polyether, Polyether formed, Polyother, Polystyrene, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS

CM 1

CRN 42573-57-9
CMF C14 H9 C16 N3 O



CM 2

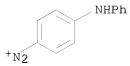
CRN 50-00-0
CMF C H2 O

CM 3

CRN 150-33-4
CMF C12 H10 N3 . 1/2 O4 S

CM 4

CRN 16072-57-4
CMF C12 H10 N3

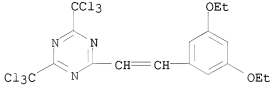


CM 5

CRN 14808-79-8
CMF O4 S

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 9 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 209530-49-4 REGISTRY
ED Entered STN: 06 Aug 1998
CN 1,3,5-Triazine, 2-[2-(3,5-diethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C17 H15 C16 N3 O2
SR CA
LC STN Files: CA, CAPLUS

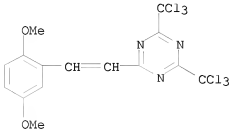


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 10 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 180308-17-2 REGISTRY

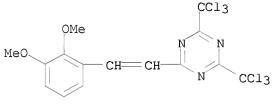
ED Entered STN: 29 Aug 1996
CN 1,3,5-Triazine, 2-[2-(2,5-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C15 H11 Cl6 N3 O2
SR CA
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 11 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 167996-75-0 REGISTRY
ED Entered STN: 22 Sep 1995
CN 1,3,5-Triazine, 2-[2-(2,3-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C15 H11 Cl6 N3 O2
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

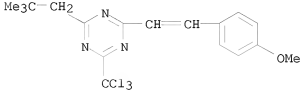


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

4 REFERENCES IN FILE CA (1907 TO DATE)
4 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 12 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 165954-20-1 REGISTRY

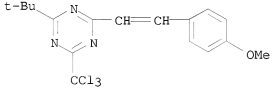
ED Entered STN: 09 Aug 1995
CN 1,3,5-Triazine, 2-(2,2-dimethylpropyl)-4-[2-(4-methoxyphenyl)ethenyl]-6-(trichloromethyl)- (CA INDEX NAME)
MF C18 H20 Cl3 N3 O
SR CA
LC STN Files: CA, CAPLUS, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 13 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 165954-13-2 REGISTRY
ED Entered STN: 09 Aug 1995
CN 1,3,5-Triazine, 2-(1,1-dimethylethyl)-4-[2-(4-methoxyphenyl)ethenyl]-6-(trichloromethyl)- (CA INDEX NAME)
MF C17 H18 Cl3 N3 O
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

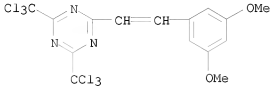


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 14 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 154880-07-6 REGISTRY
ED Entered STN: 06 May 1994
CN 1,3,5-Triazine, 2-[2-(3,5-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)

OTHER NAMES:
CN 2,4-Bis(trichloromethyl)-6-[2-(3,5-dimethoxyphenyl)ethenyl]-s-triazine
MF C15 H11 Cl6 N3 O2
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPATFULL

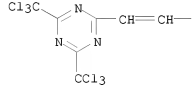


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

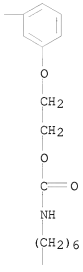
6 REFERENCES IN FILE CA (1907 TO DATE)
6 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 15 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 148515-39-3 REGISTRY
ED Entered STN: 07 Jul 1993
CN Carbamic acid, [(2,4,6-trioxo-1,3,5-triazine-1,3,5(2H,4H,6H)-triyl)tri-6,1-hexanediyl]tris-, tris[2-[3-[2-[4,6-bis(trichloromethyl)-1,3,5-triazin-2-yl]ethenyl]phenoxy]ethyl] ester (9CI) (CA INDEX NAME)
MF C69 H69 Cl18 N15 O12
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

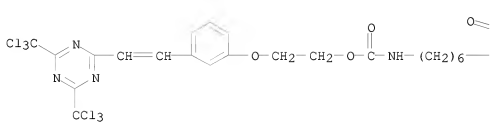
PAGE 1-A



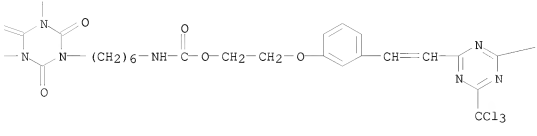
PAGE 1-B



PAGE 2-A



PAGE 2-B



— CCl_3

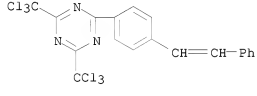
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 16 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 133926-84-8 REGISTRY
ED Entered STN: 24 May 1991
CN 2-Propenoic acid, 2-ethyl-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with 2-[4-(2-phenylethenyl)phenyl]-4,6-bis(trichloromethyl)-1,3,5-triazine (9CI) (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 1,3,5-Triazine, 2-[4-(2-phenylethenyl)phenyl]-4,6-bis(trichloromethyl)-, polymer with 2-ethyl-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI)
MF (C19 H11 Cl6 N3 . C15 H20 O6)x
CI PMS
PCT Polyacrylic, Polystyrene
SR CA
LC STN Files: CA, CAPLUS

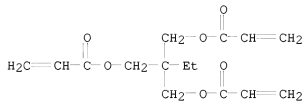
CM 1

CRN 97802-84-1
CMF C19 H11 Cl6 N3



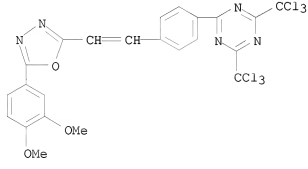
CM 2

CRN 15625-89-5
CMF C15 H20 O6



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 17 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 125775-93-1 REGISTRY
ED Entered STN: 09 Mar 1990
CN 1,3,5-Triazine, 2-[4-[2-[5-(3,4-dimethoxyphenyl)-1,3,4-oxadiazol-2-yl]ethenyl]phenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C23 H15 C16 N5 O3
SR CA
LC STN Files: CA, CAPLUS, CASREACT, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

3 REFERENCES IN FILE CA (1907 TO DATE)
3 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 18 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 125775-91-9 REGISTRY
ED Entered STN: 09 Mar 1990
CN 1,3,5-Triazine, 2-[3-[5-[2-(3,4-dimethoxyphenyl)ethenyl]-1,3,4-oxadiazol-2-yl]phenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
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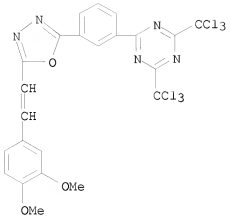
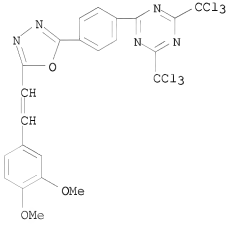
SR CA
LC STN Files: CA, CAPLUS, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 19 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 125775-86-2 REGISTRY
ED Entered STN: 09 Mar 1990
CN 1,3,5-Triazine, 2-[4-[5-[2-(3,4-dimethoxyphenyl)ethenyl]-1,3,4-oxadiazol-2-yl]phenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C23 H15 C16 N5 O3
SR CA
LC STN Files: CA, CAPLUS, USPATFULL



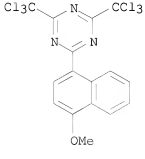
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 20 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 116746-99-7 REGISTRY
ED Entered STN: 02 Oct 1988
CN 2-Propenoic acid, polymer with 1-ethenyl-2-pyrrolidinone, 1,6-hexanediyl di-2-propenoate, isooctyl 2-propenoate and 2-(4-methoxy-1-naphthalenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine (9CI) (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 1,3,5-Triazine, 2-(4-methoxy-1-naphthalenyl)-4,6-bis(trichloromethyl)-, polymer with 1-ethenyl-2-pyrrolidinone, 1,6-hexanediyl di-2-propenoate, isooctyl 2-propenoate and 2-propenoic acid (9CI)
CN 2-Propenoic acid, 1,6-hexanediyl ester, polymer with 1-ethenyl-2-pyrrolidinone, isooctyl 2-propenoate, 2-(4-methoxy-1-naphthalenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine and 2-propenoic acid (9CI)
CN 2-Propenoic acid, isooctyl ester, polymer with 1-ethenyl-2-pyrrolidinone, 1,6-hexanediyl di-2-propenoate, 2-(4-methoxy-1-naphthalenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine and 2-propenoic acid (9CI)
CN 2-Pyrrolidinone, 1-ethenyl-, polymer with 1,6-hexanediyl di-2-propenoate, isooctyl 2-propenoate, 2-(4-methoxy-1-naphthalenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine and 2-propenoic acid (9CI)
MF (C16 H9 C16 N3 O . C12 H18 O4 . C11 H20 O2 . C6 H9 N O . C3 H4 O2)x
CI PMS
PCT Polyacrylic, Polyother, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

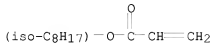
CM 1

CRN 69432-40-2
CMF C16 H9 C16 N3 O



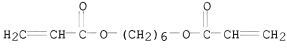
CM 2

CRN 29590-42-9
CMF C11 H20 O2
CCI IDS



CM 3

CRN 13048-33-4
CMF C12 H18 O4

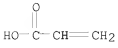


CM 4

CRN 88-12-0
CMF C6 H9 N O

CM 5

CRN 79-10-7
CMF C3 H4 O2

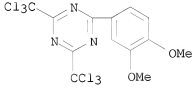


1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 21 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 113804-30-1 REGISTRY
ED Entered STN: 09 Apr 1988
CN 2-Propenoic acid, isooctyl ester, polymer with 2-(3,4-dimethoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine, 1-ethenyl-2-pyrrolidinone and 2-propenamide (9CI) (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 1,3,5-Triazine, 2-(3,4-dimethoxyphenyl)-4,6-bis(trichloromethyl)-, polymer with 1-ethenyl-2-pyrrolidinone, isooctyl 2-propenoate and 2-propenamide (9CI)
CN 2-Propenamide, polymer with 2-(3,4-dimethoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine, 1-ethenyl-2-pyrrolidinone and isooctyl 2-propenoate (9CI)
CN 2-Pyrrolidinone, 1-ethenyl-, polymer with 2-(3,4-dimethoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine, isooctyl 2-propenoate and 2-propenamide (9CI)
MF (C13 H9 C16 N3 O2 . C11 H20 O2 . C6 H9 N O . C3 H5 N O)x
CI PMS
PCT Polyacrylic, Polyether, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

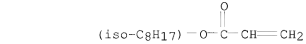
CM 1

CRN 80050-87-9
CMF C13 H9 C16 N3 O2



CM 2

CRN 29590-42-9
CMF C11 H20 O2
CCI IDS

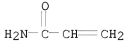


CM 3

CRN 88-12-0
CMF C6 H9 N O

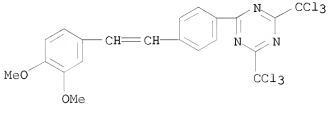
CM 4

CRN 79-06-1
CMF C3 H5 N O



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

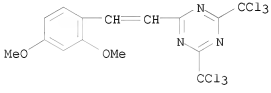
L4 ANSWER 22 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 97802-76-1 REGISTRY
ED Entered STN: 31 Aug 1985
CN 1,3,5-Triazine, 2-[4-[2-(3,4-dimethoxyphenyl)ethenyl]phenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
MF C21 H15 C16 N3 O2
SR CA
LC STN Files: CA, CAPLUS, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

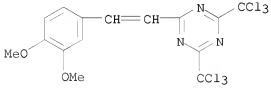
L4 ANSWER 23 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 42880-08-0 REGISTRY
ED Entered STN: 16 Nov 1984
CN 1,3,5-Triazine, 2-[2-(2,4-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
OTHER NAMES:
CN 2-(2,4-Dimethoxystyryl)-4,6-bis(trichloromethyl)-s-triazine
CN TAZ 114
MF C15 H11 C16 N3 O2
LC STN Files: CA, CAPLUS, CHEMCATS, CSCHEM, IFICDB, IFIPAT, IFIUDB, SPECINFO, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

15 REFERENCES IN FILE CA (1907 TO DATE)
15 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L4 ANSWER 24 OF 24 REGISTRY COPYRIGHT 2010 ACS on STN
RN 42880-07-9 REGISTRY
ED Entered STN: 16 Nov 1984
CN 1,3,5-Triazine, 2-[2-(3,4-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
OTHER NAMES:
CN 2-(3,4-Dimethoxystyryl)-4,6-bis(trichloromethyl)-s-triazine
CN TAZ 113
MF C15 H11 C16 N3 O2
LC STN Files: CA, CAPLUS, CHEMCATS, CSCHEM, IFICDB, IFIPAT, IFIUDB, SPECINFO, USPATFULL



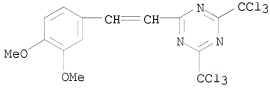
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

18 REFERENCES IN FILE CA (1907 TO DATE)
18 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> S 42880-07-9
L5 1 42880-07-9
(42880-07-9/RN)

=> D

L5 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2010 ACS on STN
RN 42880-07-9 REGISTRY
ED Entered STN: 16 Nov 1984
CN 1,3,5-Triazine, 2-[2-(3,4-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- (CA INDEX NAME)
OTHER NAMES:
CN 2-(3,4-Dimethoxystyryl)-4,6-bis(trichloromethyl)-s-triazine
CN TAZ 113
MF C15 H11 Cl6 N3 O2
LC STN Files: CA, CAPLUS, CHEMCATS, CSCHEM, IFICDB, IFIPAT, IFIUDB, SPECINFO, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

18 REFERENCES IN FILE CA (1907 TO DATE)
18 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FILE CAPLUS

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	100.24	100.46

FILE 'CAPLUS' ENTERED AT 15:59:06 ON 03 MAR 2010
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

FILE COVERS 1907 - 3 Mar 2010 VOL 152 ISS 10
FILE LAST UPDATED: 2 Mar 2010 (20100302/ED)
REVISED CLASS FIELDS (/NCL) LAST RELOADED: Dec 2009
USPTO MANUAL OF CLASSIFICATIONS THESAURUS ISSUE DATE: Dec 2009

CAplus now includes complete International Patent Classification (IPC) reclassification data for the third quarter of 2009.

CAS Information Use Policies apply and are available at:

http://www.cas.org/legal/infopolicy.html

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> S L5
L6 18 L5

=> D ALL 1-18

L6 ANSWER 1 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2007:1272565 CAPLUS <<LOGINID::20100303>>
DN 147:531561
ED Entered STN: 09 Nov 2007
TI Optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers, polarizer using it, and liquid crystal display having it with wide view angle
IN Tatsuta, Takekazu; Ushiyama, Akinobu; Kondo, Shunichi; Morishima, Shinichi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 61pp.
CODEN: JKXXAF
DT Patent
LA Japanese
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2007293180	A	20071108	JP 2006-123308	20060427
PRAI JP 2006-123308		20060427		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES

IPCI G02B0005-30 [I,A]; G02F0001-13363 [I,A]; G02F0001-1335 [I,A]; G02F0001-13 [I,C*]
IPCR G02B0005-30 [I,C]; G02B0005-30 [I,A]; G02F0001-13 [I,C]; G02F0001-1335 [I,A]; G02F0001-13363 [I,A]
FTERM 2H049/BA02; 2H049/BA06; 2H049/BA42; 2H049/BB03; 2H049/BB49; 2H049/BC02; 2H049/BC22; 2H091/FA08X; 2H091/FA08Z; 2H091/FA11X; 2H091/FA11Z; 2H091/FA12X; 2H091/FA12Z; 2H091/FB02; 2H091/FD06; 2H091/KA02; 2H091/LA12

AB The optical compensation sheet comprises (A) a substrate, (B) an alignment layer formed from a 1st composition, and (C) an optical compensation layer formed from a 2nd composition comprising liquid crystalline compds., photopolymn. initiators with a sensitive range of 330-450 nm generating halogen radicals or hydrocarbon radicals that comprise ≤8 atoms (except H), and fluoroaliph. group-containing polymers having hydrophilic groups selected from CO2H, SO3H, PO(OH)2, and their salts, wherein the 1st composition and/or the 2nd composition contain ≥1 crystal nucleating agents with nucleophilic constant 5-10. Optical compensation sheets with highly controlled alignment angles and high alignment rate of the liquid crystalline compds. are provided with this invention.

ST optical compensation sheet hybrid alignment fluoropolymer; LCD compensator
liq crystal alignment fixing fluoropolymer photoinitiator; nucleating agent hydrophilic fluoropolymer optical compensator LCD display

IT Fluoropolymers, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(acrylic; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)

IT Sulfites
Thiosulfates
RL: MOA (Modifier or additive use); USES (Uses)
(nucleating agent; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)

IT Crystal nucleating agents
Liquid crystal displays
Polarizers
(optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)

IT Polymerization catalysts
(photopolymn.; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)

IT Optical instruments
(retarders; optical compensation sheet having liquid crystals with hybrid

alignment and fluoropolymers)
IT 182154-38-7
RL: TEM (Technical or engineered material use); USES (Uses)
(alignment layer containing; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 902515-39-3 910810-39-8 927889-28-9
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(anisotropic layer containing; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 9004-36-8, CAB 551-0.2
RL: TEM (Technical or engineered material use); USES (Uses)
(anisotropic layer containing; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 1310-58-3, Potassium hydroxide, uses 7757-82-6, Disodium sulfate, uses 14280-30-9, Hydroxide, uses
RL: MOA (Modifier or additive use); USES (Uses)
(nucleating agent; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 401624-10-0P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 876594-22-8
RL: MOA (Modifier or additive use); USES (Uses)
(optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 91-44-1 27389-48-6 42880-07-9 71255-78-2 76185-67-6 91484-47-8 97802-84-1 125407-19-4 125675-34-5 145413-29-2 154880-05-4 156360-76-8 195834-08-3 253585-66-9 253585-71-6 359776-76-4 381233-66-5 405263-63-0 932020-63-8 932020-64-9 932020-65-0 932020-66-1 932020-67-2 932020-68-3
RL: CAT (Catalyst use); USES (Uses)
(photopolymn. initiator; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 9012-09-3, TD 80U
RL: TEM (Technical or engineered material use); USES (Uses)
(polarizer substrate; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)
IT 9004-35-7
RL: TEM (Technical or engineered material use); USES (Uses)
(substrate; optical compensation sheet having liquid crystals with hybrid alignment and fluoropolymers)

L6 ANSWER 2 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2007:971053 CAPLUS <<LOGINID::20100303>>

DN 147:311478
ED Entered STN: 31 Aug 2007
TI Optical compensation sheets having photopolymerized liquid crystal anisotropic layers, their manufacture, polarizing plates, and liquid crystal displays
IN Oikawa, Noriki; Yoshikawa, Susumu; Kondo, Shunichi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 35pp.
CODEN: JKXXAF
DT Patent
LA Japanese
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 25, 35, 38, 73

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2007219193	A	20070830	JP 2006-40258	20060217
PRAI	JP 2006-40258		20060217		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
	IPCI	G02B0005-30 [I,A]; B32B0007-02 [I,A]; B32B0023-08 [I,A]; B32B0023-00 [I,C*]; G02F0001-13363 [I,A]; G02F0001-1335 [I,A]; G02F0001-13 [I,C*]
	IPCR	G02B0005-30 [I,C]; G02B0005-30 [I,A]; B32B0007-02 [I,C]; B32B0007-02 [I,A]; B32B0023-00 [I,C]; B32B0023-08 [I,A]; G02F0001-13 [I,C]; G02F0001-1335 [I,A]; G02F0001-13363 [I,A]
	FTERM	2H049/BA02; 2H049/BA06; 2H049/BA42; 2H049/BB03; 2H049/BB49; 2H049/BC02; 2H049/BC05; 2H049/BC22; 2H091/FA08X; 2H091/FA08Z; 2H091/FA11X; 2H091/FA11Z; 2H091/FB02; 2H091/FB12; 2H091/HA06; 2H091/HA07; 2H091/HA09; 2H091/HA10; 2H091/HA12; 2H091/KA02; 2H091/KA10; 2H091/LA19; 4F100/AJ06A; 4F100/AK01B; 4F100/AK01C; 4F100/AK21; 4F100/AK25; 4F100/AR00A; 4F100/BA02; 4F100/BA03; 4F100/BA10A; 4F100/BA10B; 4F100/BA10C; 4F100/CA30B; 4F100/EH462; 4F100/EJ083; 4F100/EJ542; 4F100/GB41; 4F100/JA11B; 4F100/JA20C; 4F100/JB14B; 4F100/JK06; 4F100/JL05B; 4F100/JN01A; 4F100/JN30B

AB The sheets have optical retardation layers manufactured by photopolymn. of liquid crystalline compns. containing ZnL100Qm [Z = polymerizable substituent; Q = SiR1003, aldehyde, acyl, carboxyl, isocyanate, B-containing substituent; R100 = halo, alkoxy, alkyl; ≥1 of R100 = halo or alkoxy; L100 = (m + n)-valent linkage; m = 1, 2; n = 0-4] and photopolymn. initiators generating halogen radicals or C≤8 hydrocarbon radicals by excitation with light at 330-450 nm. Preferable compds. for the initiators are also given. In the manufacture, the compns. are cured at ≤80°. The sheets have good interlayer adhesion between the anisotropic layers and alignment layers.

ST optical compensation sheet anisotropic liq cryst photopolymn; LCD polarizer photopolymerized liq crystal anisotropic
IT Liquid crystal displays
Polarizers
(manufacture of optical compensation sheets having photopolymd. liquid crystal
retardation layers for polarizing plates for liquid crystal displays)
IT Optical instruments
(retarders; manufacture of optical compensation sheets having photopolymd.
liquid crystal retardation layers for polarizing plates for liquid crystal
displays)
IT 814-68-6, Acryloyl chloride 30418-59-8, 3-Aminophenylboronic acid
RL: RCT (Reactant); RACT (Reactant or reagent)
(acryloylaminophenylboronic acid manufactured from; manufacture of optical
compensation sheets having photopolymd. liquid crystal retardation layers
for polarizing plates for liquid crystal displays)
IT 91-44-1 27389-48-6 42880-07-9 71255-78-2 76185-67-6
91484-47-8 97802-84-1 125407-19-4 125675-34-5 145413-29-2
154880-05-4 156360-76-8 195834-08-3 253585-64-7 253585-66-9
253585-71-6 405263-63-0 932020-63-8 932020-64-9 932020-65-0
932020-66-1 932020-68-3
RL: CAT (Catalyst use); USES (Uses)
(initiator; manufacture of optical compensation sheets having photopolymd.
liquid crystal retardation layers for polarizing plates for liquid crystal
displays)
IT 947279-07-4P 947279-09-6P 947279-10-9P 947279-11-0P 947279-12-1P
947279-13-2P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manufacture of optical compensation sheets having photopolymd. liquid crystal
retardation layers for polarizing plates for liquid crystal displays)
IT 9004-35-7
RL: TEM (Technical or engineered material use); USES (Uses)
(support film; manufacture of optical compensation sheets having
photopolymd. liquid crystal retardation layers for polarizing plates for
liquid crystal displays)

L6 ANSWER 3 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2007:379396 CAPLUS <<LOGINID::20100303>>
DN 146:390896
ED Entered STN: 05 Apr 2007
TI Optical compensation sheet containing fixed liquid crystal, polarizer, and
liquid crystal display
IN Kondo, Shunichi
PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 23pp.
CODEN: JKXXAF
DT Patent
LA Japanese
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2007086253	A	20070405	JP 2005-273162	20050921
PRAI JP 2005-273162		20050921		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
	IPCI	G02B0005-30 [I,A]; G02F0001-1335 [I,A]; G02F0001-13363 [I,A]; G02F0001-13 [I,C*]; B32B0007-02 [I,A]; B32B0023-08 [I,A]; B32B0023-00 [I,C*]
	IPCR	G02B0005-30 [I,C]; G02B0005-30 [I,A]; B32B0007-02 [I,C]; B32B0007-02 [I,A]; B32B0023-00 [I,C]; B32B0023-08 [I,A]; G02F0001-13 [I,C]; G02F0001-1335 [I,A]; G02F0001-13363 [I,A]
	FTERM	2H049/BA02; 2H049/BA06; 2H049/BA42; 2H049/BB03; 2H049/BB42; 2H049/BB49; 2H049/BC04; 2H049/BC05; 2H049/BC22; 2H091/FA08X; 2H091/FA08Z; 2H091/FA11X; 2H091/FA11Z; 2H091/FB02; 2H091/FB12; 2H091/FC22; 2H091/FC23; 2H091/FD10; 2H091/FD15; 2H091/GA06; 2H091/GA16; 2H091/GA17; 2H091/LA12; 4F100/AJ06A; 4F100/AK01B; 4F100/AT00A; 4F100/BA02; 4F100/CA30B; 4F100/GB41; 4F100/JA11B; 4F100/JB14B; 4F100/JK06; 4F100/JL02; 4F100/JM01B; 4F100/JN01A; 4F100/JN10B

AB The sheet comprises a transparent substrate and an optical anisotropic layer containing liquid crystal compound fixed by a photopolymn. initiator having photosensitive region at 330-450 nm and generating a hydrocarbon radical with number of atoms ≤8 (except halogen radical and H). Polarizer comprises the sheet, transparent protective layer and polarizing film. Liquid crystal display having the polarizers on both sides of the liquid crystal cell is also claimed. The sheet can be formed by low energy UV ray and shows good adhesion with the anisotropic layer and alignment film.

ST optical compensation sheet liq crystal fixation photopolymn initiator; liq crystal display polarizer optical compensator

IT Liquid crystal displays
(liquid crystal display with optical compensation sheet with anisotropic layer containing liquid crystal compound fixed by photopolymn. initiator)

IT Liquid crystals, polymeric
(optical compensation sheet with anisotropic layer containing liquid crystal compound fixed by photopolymn. initiator)

IT Polymerization catalysts
(photopolymn.; optical compensation sheet with anisotropic layer containing

liquid crystal compound fixed by photopolymn. initiator)
IT Polarizers
(polarizer with optical compensation sheet with anisotropic layer containing liquid crystal compound fixed by photopolymn. initiator)
IT Optical instruments
(retarders; optical compensation sheet with anisotropic layer containing
liquid crystal compound fixed by photopolymn. initiator)
IT 180570-45-0P 663626-57-1P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(optical compensation sheet with anisotropic layer containing liquid crystal
compound fixed by photopolymn. initiator)
IT 91-44-1 27389-48-6 42880-07-9 71255-78-2 76185-67-6
91484-47-8 97802-84-1 125407-19-4 125675-34-5 145413-29-2
154880-05-4 156360-76-8 195834-08-3 253585-66-9 253585-71-6
359776-76-4 405263-63-0 932020-63-8 932020-64-9 932020-65-0
932020-66-1 932020-67-2 932020-68-3
RL: CAT (Catalyst use); USES (Uses)
(photopolymn. initiator; optical compensation sheet with anisotropic layer containing liquid crystal compound fixed by photopolymn. initiator)
IT 9004-35-7
RL: TEM (Technical or engineered material use); USES (Uses)
(substrate; optical compensation sheet with anisotropic layer containing
liquid crystal compound fixed by photopolymn. initiator)

L6 ANSWER 4 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2006:1313648 CAPLUS <<LOGINID::20100303>>
DN 147:223121
ED Entered STN: 15 Dec 2006
TI Studies of synthesis of triazine derivatives and their properties as photoacid generators for photoresists
AU Wang, Jian; Wang, Wen-guang; Zhang, Wei-min; Pu, Jia-ling
CS Beijing Area Major Lab of Printing & Packaging Material and Technology, Beijing Institute of Graphic, Xinghua Beilu, Beijing, 102600, Peop. Rep. China
SO Ganguang Kexue Yu Guang Huaxue (2006), 24(6), 436-443
CODEN: GKKHE9; ISSN: 1000-3231
PB Kexue Chubanshe
DT Journal
LA Chinese
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
AB Five triazine derivs., such as 2-(4-methoxystyryl)-4,6-bis(trichloromethyl)-1,3,5-triazine and 2-(3,4-dimethoxystyryl)-4,6-bis(trichloromethyl)-1,3,5-triazine (I), were prepared and characterized by 1H NMR and mass spectra. Quantum yields of decomposition and acid formation of I in acetonitrile in different concns. were
measured when exposed at 405 and 365 nm. It was found that quantum yields

are strongly dependent on the wavelengths of light, rather than on their concns. in acetonitrile. Decomposition and acid formation in acetonitrile of I
are more efficient at 405 nm than at 365 nm.
ST styryl triazine compd photoacid generator photoresist
IT Photoresists
(preparation of triazine derivs. as photoacid generators for photoresists)
IT 42573-57-9P 42880-07-9P 123319-90-4P 944727-17-7P 944727-18-8P
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(preparation of triazine derivs. as photoacid generators for photoresists)
IT 120-14-9 120-21-8 123-11-5, reactions 949-42-8 4181-05-9 7570-45-8
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of triazine derivs. as photoacid generators for photoresists)

L6 ANSWER 5 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2006:655656 CAPLUS <<LOGINID::20100303>>
DN 145:113605
ED Entered STN: 07 Jul 2006
TI Radiation-sensitive negative resin compositions, dielectric films therefrom, and organic electroluminescence displays therewith
IN Abe, Nobuki
PA Nippon Zeon Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 20 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2006179423	A	20060706	JP 2004-374128	20041224
PRAI	JP 2004-374128		20041224		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
	IPCI	H05B0033-22 [I,A]; G03F0007-004 [I,A]; G09F0009-30 [I,A]; H01L0027-32 [I,A]; H01L0027-28 [I,C*]; H05B0033-10 [I,A]; H05B0033-12 [I,A]; H01L0051-50 [I,A]
	FTERM	2H025/AA03; 2H025/AA13; 2H025/AA20; 2H025/AB17; 2H025/AB20; 2H025/AC01; 2H025/AD01; 2H025/BE00; 2H025/CB17; 2H025/CB28; 2H025/CB45; 2H025/CC17; 3K007/AB11; 3K007/AB18; 3K007/BA06; 3K007/DB03; 3K007/EB00; 3K007/FA01; 5C094/AA31; 5C094/BA27; 5C094/DA15; 5C094/FB15

AB The compns. comprise (a) alkali-soluble resins (e.g., novolak resins, polyhydroxystyrene), (b) photoacid generators, and (c) curing agents

(e.g., melamines, epoxides). The compns. form edge-rounded dielec. films with less shrinkage.
ST org electroluminescent display dielec film neg photoimaging; novolak melamine resin photoacid generator EL display insulator; display edge rounded insulator film shrinkage prevention
IT Electroluminescent devices
(displays; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT Luminescent screens
(electroluminescent; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT Phenolic resins, uses
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(novolak; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT Photoimaging materials
(photopolymerizable; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT Dielectric films
(radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT Aminoplasts
RL: RCT (Reactant); TEM (Technical or engineered material use); RACT (Reactant or reagent); USES (Uses)
(radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT 9003-08-1, Melamine resin
RL: RCT (Reactant); TEM (Technical or engineered material use); RACT (Reactant or reagent); USES (Uses)
(Cymel 300, Nikalac MW 30HM, curing agents; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(LC 5080G, LC 4050G; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT 24979-70-2, S 4P
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(S 4P; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
IT 42880-07-9 156360-76-8
RL: CAT (Catalyst use); TEM (Technical or engineered material use); USES (Uses)
(photoacid generators; radiation-sensitive neg. resin compns. forming edge-rounded dielec. films for EL displays)
OSC.G 2 THERE ARE 2 CAPLUS RECORDS THAT CITE THIS RECORD (2 CITINGS)
UPOS.G Date last citing reference entered STN: 16 Feb 2009
OS.G CAPLUS 2008:774281; 2008:283298

L6 ANSWER 6 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2005:1283069 CAPLUS <<LOGINID::20100303>>
DN 144:43286

ED Entered STN: 08 Dec 2005
TI Radiation sensitive composition for color filter, method of forming the color filter under low oxygen atmosphere, and liquid crystal display
IN Koyama, Kiyoshi; Numata, Atsushi; Kobayashi, Kazuhiro
PA Jsr Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 22 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G02B005-20
ICS G03F007-004; H01L021-027
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005338117	A	20051208	JP 2004-152781	20040524

PRAI JP 2004-152781 20040524
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2005338117	ICM	G02B005-20
	ICS	G03F007-004; H01L021-027
	IPCI	G02B0005-20 [ICM,7]; G03F0007-004 [ICS,7]; H01L0021-027
		[ICS,7]; H01L0021-02 [ICS,7,C*]
	FTERM	2H025/AA02; 2H025/AB13; 2H025/AC01; 2H025/AD01; 2H025/BC13; 2H025/BC42; 2H025/CA00; 2H025/CB42; 2H025/CC11; 2H025/CC20; 2H025/FA03; 2H025/FA17; 2H048/BA02; 2H048/BA45; 2H048/BA47; 2H048/BA48; 2H048/BB02; 2H048/BB42

AB Disclosed is a radiation sensitive composition comprising a pigment, a dispersing agent, an alkali-soluble resin, a polyfunctional monomer, and a photopolymn. initiator, wherein a content of the photopolymn. initiator on the basis of the polyfunctional monomer 100 weight parts is 0.5-5 weight parts.
Also disclosed is a process, in which radiation (e.g., UV light) is directed to a film of said composition under a low O2 atmospheric, preferably, a reduced pressure. A liquid crystal display having said color filter is also claimed.
ST radiation sensitive compn color filter liq crystal display; UV photolithog photosensitive compn
IT Liquid crystal displays
Optical filters
Photolithography
(Radiation sensitive composition for LCD color filter exposed under reduced oxygen concentration)
IT 29570-58-9, Dipentaerythritol hexaacrylate

RL: DEV (Device component use); USES (Uses)
(Radiation sensitive composition for LCD color filter exposed under reduced oxygen concentration)
IT 7782-44-7, Oxygen, miscellaneous
RL: MSC (Miscellaneous)
(Radiation sensitive composition for LCD color filter exposed under reduced oxygen concentration)
IT 7189-82-4 42880-07-9 119313-12-1
RL: CAT (Catalyst use); USES (Uses)
(photopolymn. initiator; Radiation sensitive composition for LCD color filter exposed under reduced oxygen concentration)

L6 ANSWER 7 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2002:748352 CAPLUS <<LOGINID::20100303>>
DN 137:286432
ED Entered STN: 03 Oct 2002
TI Negative-working photoresist compositions containing specific photoacid generator and method for pattern formation using the same
IN Kashiwagi, Mikifumi; Kusu, Tetsuaki; Mitao, Tokuyuki
PA Nippon Zeon Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F007-004; C08K005-3492; C08L101-14; G03F007-40
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2002287341	A	20021003	JP 2001-84404	20010323
JP 4380075	B2	20091209		
PRAI JP 2001-84404		20010323		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2002287341	ICM	G03F007-004
	ICS	G03F007-004; C08K005-3492; C08L101-14; G03F007-40
	IPCI	G03F0007-004 [I,A]; C08K0005-3492 [I,A]; C08K0005-00 [I,C*]; C08L0101-14 [I,A]; C08L0101-00 [I,C*]; G03F0007-40 [I,A]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; C08K0005-00 [I,C*]; C08K0005-3492 [I,A]; C08L0101-00 [I,C*]; C08L0101-14 [I,A]; G03F0007-40 [I,C*]; G03F0007-40 [I,A]

AB The title composition contains alkali solubilizable resins, a photoacid generator, a cross linking agent, and a solvent, wherein the photoacid generator has 300-450 nm λmax and ≥2500 mol absorbance(ε), and satisfies the equation: ε≥(400Xλmax)-120000. The composition shows the good storageability and provide pattern profile of reverse taper, which is

suitable as insulative ribs in organic EL display panels.
ST neg working photoresist compn photoacid generator
IT Light-sensitive materials
Negative photoresists
(neg.-working photoresist compns. and method for pattern formation using same)
IT Electroluminescent devices
(panels; neg.-working photoresist compns. and method for pattern formation using same)
IT 1898-74-4, s-Triazine,2,4-diphenyl- 42573-57-9, 1,3,5-Triazine,2-[2-(4-methoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- 42880-07-9, 1,3,5-Triazine,2-[2-(3,4-dimethoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)- 79771-30-5 202074-55-3, 1,3,5-Triazine,2-[2-(3-chloro-4-methoxyphenyl)ethenyl]-4,6-bis(trichloromethyl)
RL: CAT (Catalyst use); USES (Uses)
(photopolymn. initiator; neg.-working photoresist compns. and method for pattern formation using same)
OSC.G 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD (1 CITINGS)
UPOS.G Date last citing reference entered STN: 16 Feb 2009
OS.G CAPLUS 2004:780749

L6 ANSWER 8 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2000:638197 CAPLUS <<LOGINID::20100303>>
DN 133:259335
ED Entered STN: 14 Sep 2000
TI Actinic ray-sensitive resist composition for manufacture of liquid crystal
display color filter
IN Sakurai, Koichi; Nagatsuka, Tomio; Kamii, Hideyuki; Watanabe, Takeshi
PA JSR Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 20 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G02B005-20
ICS C08K005-20; C08L101-12; G03F007-004; G03F007-028
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000249826	A	20000914	JP 1999-55204	19990303

PRAI JP 1999-55204 19990303
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2000249826	ICM	G02B005-20
	ICS	C08K005-20; C08L101-12; G03F007-004; G03F007-028
	IPCI	G02B0005-20 [ICM,7]; C08K0005-20 [ICS,7]; C08L0101-12 [ICS,7]; G03F0007-004 [ICS,7]; G03F0007-028 [ICS,7]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; C08K0005-00 [I,C*]; C08K0005-20 [I,A]; C08L0101-00 [I,C*]; C08L0101-12 [I,A]; G02B0005-20 [I,C*]; G02B0005-20

[I,A]; G03F0007-028 [I,C*]; G03F0007-028 [I,A]
AB The title composition comprises (A) colorant, (B) alkaline-soluble resin, (C) polyfunctional monomer, (D) monofunctional monomer CH2:CR1CONH(CH2)iC(OCmH2m+1)HCO2CnH2n+1 [R1 = H, CH3; i = 0-2; m = 1-4; n = 1-4], and (E) photopolymn. initiator. The obtained filter shows excellent scratch-resistance.
ST photoresist compn methacrylamide acrylamide photopolymn initiator color filter manuf
IT Liquid crystal displays
Photoresists
(actinic ray-sensitive resist composition for manufacture of liquid crystal display color filter)
IT 141655-30-3, Benzyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid copolymer 215383-54-3, Benzyl methacrylate-methacrylic acid-N-phenylmaleimide-styrene copolymer 283597-64-8, Benzyl methacrylate-methacrylic acid-mono(2-acryloyloxyethyl)succinate-N-phenylmaleimide-styrene copolymer 283605-07-2, Methacrylic acid-styrene-benzyl methacrylate-glycerol monomethacrylate-N-phenylmaleimide copolymer 294849-96-0, Benzyl methacrylate-ω-carboxylpolycaprolactone monoacrylate-glycerol monomethacrylate-methacrylic acid-N-phenylmaleimide-styrene copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(alkaline soluble polymer in actinic ray-sensitive resist composition for manufacture of liquid crystal display color filter)
IT 294850-08-1P 294850-11-6P 294850-14-9P 294850-17-2P 294850-20-7P 294850-23-0P 294850-26-3P
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(color filter of liquid crystal display obtained from actinic ray-sensitive resist composition)
IT 147-14-8, C.I.Pigment Blue 15:6 215247-95-3, C.I.Pigment Violet 23
RL: TEM (Technical or engineered material use); USES (Uses)
(colorant in actinic ray-sensitive resist composition for manufacture of liquid crystal display blue filter)
IT 1328-53-6, C.I.Pigment Green 7 5567-15-7, C.I.Pigment Yellow 83 14302-13-7, C.I.Pigment Green 36 30125-47-4, C.I.Pigment Yellow 138 872613-79-1, C.I.Pigment Yellow 150
RL: TEM (Technical or engineered material use); USES (Uses)
(colorant in actinic ray-sensitive resist composition for manufacture of liquid crystal display green filter)
IT 128-69-8, C.I.Pigment Red 224 4051-63-2, C.I.Pigment Red 177 36888-99-0, C.I.Pigment Yellow 139 84632-65-5, C.I.Pigment Red 254
RL: TEM (Technical or engineered material use); USES (Uses)
(colorant in actinic ray-sensitive resist composition for manufacture of liquid crystal display red filter)
IT 77402-03-0 77402-15-4 141392-64-5 294849-99-3
RL: TEM (Technical or engineered material use); USES (Uses)
(monofunctional monomer in actinic ray-sensitive resist composition for

manufacture of liquid crystal display color filter)
IT 90-93-7, 4,4'-Bis(diethylamino)benzophenone 149-30-4,
2-Mercaptobenzothiazole 7189-83-5 42880-07-9 119313-12-1,
2-Benzyl-2-dimethylamino-1-(4-morpholinophenyl)butanone
RL: TEM (Technical or engineered material use); USES (Uses)
(photopolymn. initiator in actinic ray-sensitive resist composition
for
manufacture of liquid crystal display color filter)
IT 29570-58-9, Dipentaerythritol hexaacrylate
RL: TEM (Technical or engineered material use); USES (Uses)
(polyfunctional monomer in actinic ray-sensitive resist composition
for
manufacture of liquid crystal display color filter)
OSC.G 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD (1 CITINGS)
UPOS.G Date last citing reference entered STN: 21 Sep 2009
OS.G CAPLUS 2009:1108696

L6 ANSWER 9 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2000:532752 CAPLUS <<LOGINID::20100303>>
DN 133:170304
ED Entered STN: 04 Aug 2000
TI UV-sensitive color filter composition
IN Sakurai, Koichi; Yoshida, Koichiro; Watanabe, Takeshi
PA JSR Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 24 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-085
ICS C08F002-48; C08F004-00; G02B005-20; G03F007-004
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000214592	A	20000804	JP 1999-15848	19990125
JP 4135247	B2	20080820		
PRAI JP 1999-15848		19990125		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2000214592	ICM	G03F007-085
	ICS	C08F002-48; C08F004-00; G02B005-20; G03F007-004
	IPCI	G03F0007-085 [I,A]; G03F0007-028 [I,A]; G03F0007-004 [I,A]; C08F0002-48 [I,A]; C08F0002-46 [I,C*]; C08F0004-00 [I,A]; G02B0005-20 [I,A]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; C08F0002-46 [I,C*]; C08F0002-48 [I,A]; C08F0004-00 [I,C*]; C08F0004-00 [I,A]; G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G03F0007-085 [I,C*]; G03F0007-085 [I,A]; G03F0007-028 [I,C]; G03F0007-028 [I,A]

AB The invention relates to an UV-sensitive color filter composition
containing: (A) a
colorant; (B) an alkali soluble resin; (C) a monomer having plural
functional

groups; (D) a photopolymn. initiator; and (E) an oxetane. The composition
provides the increased hardness of the color filter film.
ST color filter compn
IT Optical filters
Optical imaging devices
(UV-sensitive color filter composition)
IT 90-93-7, 4,4'-Bis(diethylamino)benzophenone 149-30-4,
2-Mercaptobenzothiazole 3047-32-3 5567-15-7, C.I. Pigment Yellow 83
7189-83-5 14302-13-7, C.I. Pigment Green 36 29570-58-9,
Dipentaerythritol hexaacrylate 30125-47-4, C.I. Pigment Yellow 138
42573-57-9 42880-07-9 71255-78-2 119313-12-1,
2-Benzyl-2-dimethylamino-1-(4-morpholinophenyl)butanone 141655-30-3,
Methacrylic acid-2-hydroxyethyl methacrylate-benzyl methacrylate copolymer
142627-97-2 283597-64-8, Methacrylic acid-mono(2-acryloyloxyethyl)
succinate-styrene-benzyl methacrylate-N-phenylmaleimide copolymer
283605-07-2, Methacrylic acid-styrene-benzyl methacrylate-glycerol
monomethacrylate-N-phenylmaleimide copolymer 872613-79-1, C.I. Pigment
Yellow 150
RL: TEM (Technical or engineered material use); USES (Uses)
(UV-sensitive color filter composition)

L6 ANSWER 10 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 2000:151333 CAPLUS <<LOGINID::20100303>>
DN 132:201079
ED Entered STN: 07 Mar 2000
TI Dye with protected hydroxy group and thermal-transfer printing material
IN Furukawa, Minoru; Hanmura, Masahiro; Eguchi, Hiroshi
PA Dai Nippon Printing Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 28 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM B41M005-38
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 41
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2000071631	A	20000307	JP 1998-247136	19980901
PRAI JP 1998-247136		19980901		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2000071631	ICM	B41M005-38
	IPCI	B41M0005-38 [ICM,7]
	IPCR	B41M0005-382 [I,A]; B41M0005-26 [I,C*]; B41M0005-385 [I,A]; B41M0005-388 [I,A]; B41M0005-39 [I,A]; B41M0005-392 [I,A]; B41M0005-50 [I,C*]; B41M0005-50 [I,A]; B41M0005-52 [I,A]

OS MARPAT 132:201079
AB The dye is protected at least partially on OH by a group, which is

converted into a volatile substance after releasing from the dye. The protecting group leaves a portion linkable with OH, i.e., the exact original dye is obtained after removal of the protecting group. The thermal-transfer printing material consists of a material with a layer containing the dye protected by the group leaving under heat and another material having an image-accepting layer containing an acid for accelerating
removal of the protecting group. The dye-containing layer and the image-accepting layer are laminated and patternwise heated to give an image on the accepting layer. The thermally transfered image shows prevention of discoloration caused by the residue of protecting group.
ST dye protecting group thermal transfer printing; acid catalyst protecting group removal acceleration; hydroxy group protected dye thermal printing
IT Dyes
Thermal-transfer printing materials
(dye protected on hydroxy group for thermal-transfer printing)
IT Dissociation catalysts
(for accelerating removal of protecting group from dye in thermal-transfer printing material)
IT 79014-78-1 107689-41-8 109194-20-9 123520-93-4 147613-95-4
260061-37-8 260061-38-9 260061-39-0 260061-40-3 260061-41-4
260061-42-5 260061-43-6 260061-44-7 260061-45-8 260061-59-4
260061-60-7 260061-64-1 260061-67-4
RL: TEM (Technical or engineered material use); USES (Uses)
(dye protected on hydroxy group for thermal-transfer printing)
IT 104-15-4, uses 120-18-3, 2-Naphthalene sulfonic acid 949-42-8
1226-42-2 3584-23-4 5551-72-4 6293-66-9 6542-67-2 10287-53-3
24504-22-1 34684-40-7 41580-58-9 42573-57-9 42880-07-9
42880-08-0 42880-12-6 55048-39-0 57835-99-1 57840-38-7
61358-23-4 61358-25-6 62051-09-6 63226-13-1 66003-76-7
66003-78-9 69432-40-2 71255-78-2 71449-78-0 73674-58-5
80050-87-9 81416-37-7 82424-53-1 83697-53-4 83697-56-7
84563-54-2 85342-62-7 87709-41-9 90555-42-3 115298-63-0
116808-67-4 127279-74-7 142342-33-4 151052-45-8 160481-39-0
179419-32-0 193345-23-2 194999-82-1 194999-85-4 202074-55-3
260061-46-9 260061-47-0 260061-48-1 260061-49-2 260061-51-6
260061-52-7 260061-53-8 260061-55-0 260061-57-2 260061-58-3
RL: CAT (Catalyst use); USES (Uses)
(for accelerating removal of protecting group from dye in thermal-transfer printing material)

L6 ANSWER 11 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 1997:577009 CAPLUS <<LOGINID::20100303>>
DN 127:177245
OREF 127:34346h,34347a
ED Entered STN: 11 Sep 1997
TI Colored photosensitive acrylic resin compositions using safe solvents and color filters using the same
IN Tateno, Masahiko; Hidaka, Takahiro
PA Sekisui Chemical Co. Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DT Patent
LA Japanese

IC ICM G02B005-20
ICS C08F290-06; C08L033-04; G03F007-004; G03F007-027; G03F007-029
CC 37-6 (Plastics Manufacture and Processing)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 09178932	A	19970711	JP 1995-340853	19951227
PRAI JP 1995-340853		19951227		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 09178932	ICM	G02B005-20
	ICS	C08F290-06; C08L033-04; G03F007-004; G03F007-027; G03F007-029
	IPCI	G02B0005-20 [ICM,6]; C08F0290-06 [ICS,6]; C08L0033-04 [ICS,6]; G03F0007-004 [ICS,6]; G03F0007-027 [ICS,6]; G03F0007-029 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; C08F0290-00 [I,C*]; C08F0290-00 [I,A]; C08F0290-06 [I,A]; C08L0033-00 [I,C*]; C08L0033-04 [I,A]; G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G03F0007-027 [I,C*]; G03F0007-027 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]

AB The title compns. use Et lactate as the solvent and polyfunctional monomers chosen from pentaerythritol acrylate, ethoxylated trimethylolpropane triacrylate, and dipentaerythritol hexaacrylate. A binder resin was prepared from acrylic acid 15, 2-hydroxyethyl methacrylate 35, Bu methacrylate 35, and Me methacrylate 15 parts and used as 10%-solids solution in Et lactate with PE-3A crosslinker and Irgacure 369, Kayacure CPTX, and Kayacure DMBI, for testing without pigment.

ST color filter photosensitive acrylic compn

IT Optical filters
(colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)

IT Crosslinking catalysts
(photochem.; colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)

IT 142770-42-1, 1-Chloro-4-propoxythioxanthone
RL: CAT (Catalyst use); USES (Uses)
(Kayacure CPTX; colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)

IT 21245-01-2, Isoamyl 4-(dimethylamino)benzoate
RL: CAT (Catalyst use); USES (Uses)
(Kayacure DMBI; colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)

IT 160509-79-5, 2-(3,4,5-Trimethoxystyryl)-4,6-bis(trichloromethyl)-s-triazine
RL: CAT (Catalyst use); USES (Uses)
(TAZ 111; colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)

IT 42880-07-9, 2-(3,4-Dimethoxystyryl)-4,6-bis(trichloromethyl)-s-triazine
RL: CAT (Catalyst use); USES (Uses)
(TAZ 113; colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)
IT 151052-45-8, 2-(2-Methoxystyryl)-4,6-bis(trichloromethyl)-s-triazine
RL: CAT (Catalyst use); USES (Uses)
(TAZ 118; colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)
IT 119313-12-1, Irgacure 369
RL: CAT (Catalyst use); USES (Uses)
(colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)
IT 193827-91-7P 193827-94-0P 193827-96-2P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)
IT 97-64-3, Ethyl lactate
RL: NUU (Other use, unclassified); USES (Uses)
(colored photosensitive acrylic resin compns. using safe solvents and color filters using the same)

L6 ANSWER 12 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 1996:455321 CAPLUS <<LOGINID::20100303>>
DN 125:100184
OREF 125:18559a,18562a
ED Entered STN: 01 Aug 1996
TI Photoresist composition and etching method
IN Yoshimoto, Hiroshi
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F007-038; G03F007-039
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 08110637	A	19960430	JP 1994-244425	19941007
PRAI JP 1994-244425		19941007		

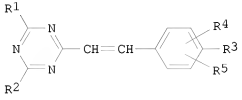
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 08110637	ICM	G03F007-004
	ICS	G03F007-038; G03F007-039
	IPCI	G03F0007-004 [ICM,6]; G03F0007-038 [ICS,6]; G03F0007-039 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]; G03F0007-039 [I,C*];

G03F0007-039 [I,A]

OS MARPAT 125:100184

GI



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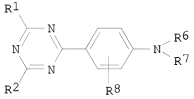
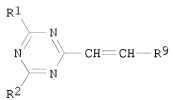


II



III

AB The photoresist composition comprises (a) a novolak resin, (b) an acid crosslinking compound, (c) propylene glycol monoalkyl ether and/or its esters, (d) a photosensitive s-triazine compound I, and (e) another photosensitive s-triazine compound selected from I, II, and III [R1-2 = C1-3 haloalkyl, haloalkenyl; R3 = halo, (substituted) alkyl, alkoxy, (substituted) aryl; R4-5 = H, halo, (substituted) alkyl, alkoxy, (substituted) aryl; R6-7 = H, (substituted) alkyl, alkoxy, (substituted) aryl; R8 = H, halo, alkyl, alkoxy; R9 = heterocyclyl, aryl which may be substituted at positions other than 4]. The etching method comprises (1) coating the photoresist on a substrate, (2) patternwise exposing the photoresist, and (3) wet-etching the substrate using the patterned photoresist. The photoresist shows high sensitivity, good coating property, prevents the generation of developing residue, and is useful for manufacture of semiconductor devices.

ST photoresist triazine compd novolak resin; etching method photoresist

IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak, photoresist composition containing triazine compound as photosensitive acid generator)

IT Resists
(photo-, photoresist composition containing triazine compound as photosensitive acid generator)

IT 9003-08-1, Nikalac mw 30m
RL: TEM (Technical or engineered material use); USES (Uses)

(acid crosslinking agent; photoresist composition containing triazine compound as
photosensitive acid generator)
IT 42573-57-9 42880-05-7 42880-06-8 42880-07-9 42880-08-0
129509-22-4 151052-44-7 151052-45-8 154880-07-6 155050-58-1
156360-76-8 160509-79-5 166891-15-2 179037-28-6 179037-29-7
179037-30-0
RL: CAT (Catalyst use); USES (Uses)
(photoresist composition containing triazine compound as photosensitive acid
generator)
IT 84540-57-8D, Propylene glycol monomethyl ether acetate, solvent
RL: NUU (Other use, unclassified); USES (Uses)
(photoresist composition containing triazine compound as photosensitive acid
generator)
IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(photoresist composition containing triazine compound as photosensitive acid
generator)

L6 ANSWER 13 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 1996:323247 CAPLUS <<LOGINID::20100303>>
DN 124:356261
OREF 124:65901a,65904a
ED Entered STN: 04 Jun 1996
TI Color filter for liquid-display panel
IN Kashiwazaki, Akio; Sato, Hiroshi; Shirota, Katsuhiro; Yokoi, Hideto; Miyazaki, Takeshi; Shiba, Shoji
PA Canon K. K., Japan
SO Eur. Pat. Appl., 36 pp.
CODEN: EPXXDW
DT Patent
LA English
IC ICM G02B005-20
ICS G02F001-1335
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 704722	A2	19960403	EP 1995-115446	19950929
	EP 704722	A3	19960828		
	EP 704722	B1	20021218		
	R: DE, FR, GB, IT				
	JP 08227011	A	19960903	JP 1995-247970	19950926
	US 5716739	A	19980210	US 1995-536781	19950929
	KR 175420	B1	19990320	KR 1995-33427	19950930
PRAI	JP 1994-237096	A	19940930		
	JP 1994-319991	A	19941222		
	JP 1995-247970	A	19950926		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES

EP 704722	ICM	G02B005-20
	ICS	G02F001-1335
	IPCI	G02B0005-20 [ICM,6]; G02F0001-1335 [ICS,6]; G02F0001-13 [ICS,6,C*]
	IPCR	B41J0002-01 [I,C*]; B41J0002-01 [I,A]; B41M0005-00 [I,C*]; B41M0005-00 [I,A]; B41M0005-50 [I,C*]; B41M0005-50 [I,A]; B41M0005-52 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-56 [I,A]; C08G0059-00 [I,C*]; C08G0059-50 [I,A]; G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G02B0005-22 [I,C*]; G02B0005-22 [I,A]; G02F0001-13 [I,C*]; G02F0001-1335 [I,A]
	ECLA	G02B005/22D
JP 08227011	IPCI	G02B0005-20 [ICM,6]; B41J0002-01 [ICS,6]; C08F0020-56 [ICS,6]; C08F0020-00 [ICS,6,C*]; C08G0059-50 [ICS,6]; C08G0059-00 [ICS,6,C*]; G02F0001-1335 [ICS,6]; G02F0001-13 [ICS,6,C*]
	IPCR	B41J0002-01 [I,C*]; B41J0002-01 [I,A]; B41M0005-00 [I,C*]; B41M0005-00 [I,A]; B41M0005-50 [I,C*]; B41M0005-50 [I,A]; B41M0005-52 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-56 [I,A]; C08G0059-00 [I,C*]; C08G0059-50 [I,A]; G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G02B0005-22 [I,C*]; G02B0005-22 [I,A]; G02F0001-13 [I,C*]; G02F0001-1335 [I,A]
	ECLA	G02B005/22D
US 5716739	IPCI	G02B0005-20 [ICM,6]; G02F0001-1335 [ICS,6]; G02F0001-13 [ICS,6,C*]
	IPCR	B41J0002-01 [I,C*]; B41J0002-01 [I,A]; B41M0005-00 [I,C*]; B41M0005-00 [I,A]; B41M0005-50 [I,C*]; B41M0005-50 [I,A]; B41M0005-52 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-56 [I,A]; C08G0059-00 [I,C*]; C08G0059-50 [I,A]; G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G02B0005-22 [I,C*]; G02B0005-22 [I,A]; G02F0001-13 [I,C*]; G02F0001-1335 [I,A]
	NCL	430/007.000; 347/106.000; 427/164.000; 427/492.000; 427/493.000; 427/511.000; 427/512.000; 430/321.000
	ECLA	G02B005/22D
KR 175420	IPCI	G02F0001-1335 [ICM,7]; G02F0001-13 [ICM,7,C*]
	IPCR	B41J0002-01 [I,C*]; B41J0002-01 [I,A]; B41M0005-00 [I,C*]; B41M0005-00 [I,A]; B41M0005-50 [I,C*]; B41M0005-50 [I,A]; B41M0005-52 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-56 [I,A]; C08G0059-00 [I,C*]; C08G0059-50 [I,A]; G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G02B0005-22 [I,C*]; G02B0005-22 [I,A]; G02F0001-13 [I,C*]; G02F0001-1335 [I,A]
	ECLA	G02B005/22D

ASSIGNMENT HISTORY FOR US PATENT AVAILABLE IN LSUS DISPLAY FORMAT

AB The title color filter is prepared by ink-jet printing of a material having

an ink-receiving layer comprising a homopolymer of a monomer having the structure CH2=CR1[CON(CH2OR2)(CH2OR3)]] (R1 = H or methyl; R2, R3 = H or alkyl having 1-5 C atoms) or its copolymer with one or more other vinyl monomers.

ST color filter ink jet vinyl polymer; liq crystal display color filter

IT Optical filters
(color; preparation by ink-jet printing on ink-receiving layers containing vinyl polymers for liquid-crystal display devices)

IT Optical imaging devices
(electrooptical liquid-crystal, color filters prepared by ink-jet printing on ink-receiving layers containing vinyl polymers for)

IT Printing, nonimpact
(ink-jet, on ink-receiving layers containing vinyl polymers for color filter preparation for liquid-crystal display devices)

IT 313-39-3, Diphenyliodonium tetrafluoroborate 3584-23-4 6542-67-2 24504-22-1 42573-57-9 42880-07-9 52754-92-4, Diphenyliodonium hexafluoroantimonate 58109-40-3, Diphenyliodonium hexafluorophosphate 66003-76-7 66003-78-9 69432-40-2 75482-18-7 84563-54-2 116808-67-4 176979-01-4 176979-02-5 176979-03-6 176979-04-7 176979-06-9
RL: TEM (Technical or engineered material use); USES (Uses)
(in preparing ink-receiving layers for color filter preparation by ink-jet printing for liquid-crystal display devices)

OSC.G 6 THERE ARE 6 CAPLUS RECORDS THAT CITE THIS RECORD (8 CITINGS)

UPOS.G Date last citing reference entered STN: 22 Jan 2010

OS.G CAPLUS 2009:267586; 2009:1618157; 2007:359100; 2009:490065; 2001:472600;
2000:699107

L6 ANSWER 14 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN

AN 1995:753433 CAPLUS <<LOGINID::20100303>>

DN 123:156423

OREF 123:27615a,27618a

ED Entered STN: 24 Aug 1995

TI Negative-type photoresist composition

IN Yoshimoto, Hiroshi; Kokubo, Tadayoshi

PA Fuji Photo Film Co., Ltd., Japan

SO Ger. Offen., 12 pp.
CODEN: GWXXBX

DT Patent

LA German

IC ICM G03F007-039
ICS C08L061-06; C08K005-3492; C08J003-28; C08J003-24; C08F002-48; C08F026-06; C08F012-26

ICA C08F024-00; C08F028-06

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

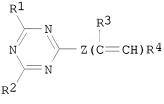
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4435791	A1	19950413	DE 1994-4435791	19941006

JP 07140653 A 19950602 JP 1993-251778 19931007
PRAI JP 1993-251778 A 19931007
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 4435791	ICM	G03F007-039
	ICS	C08L061-06; C08K005-3492; C08J003-28; C08J003-24; C08F002-48; C08F026-06; C08F012-26
	ICA	C08F024-00; C08F028-06
	IPCI	G03F0007-039 [ICM,6]; C08L0061-06 [ICS,6]; C08L0061-00 [ICS,6,C*]; C08K0005-3492 [ICS,6]; C08K0005-00 [ICS,6,C*]; C08J0003-28 [ICS,6]; C08J0003-24 [ICS,6]; C08F0002-48 [ICS,6]; C08F0002-46 [ICS,6,C*]; C08F0026-06 [ICS,6]; C08F0026-00 [ICS,6,C*]; C08F0012-26 [ICS,6]; C08F0012-00 [ICS,6,C*]; C08F0024-00 [ICA,6]; C08F0028-06 [ICA,6]; C08F0028-00 [ICA,6,C*]
	IPCR	C08F0002-46 [I,C*]; C08F0002-48 [I,A]; C08K0005-00 [I,C*]; C08K0005-3492 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]; H01L0021-02 [I,C*]; H01L0021-02 [I,A]; H01L0021-30 [I,A]
	ECLA	C08K005/3492+L61/06; G03F007/004D; G03F007/029A
JP 07140653	IPCI	G03F0007-029 [ICM,6]; G03F0007-004 [ICS,6]; G03F0007-038 [ICS,6]; H01L0021-02 [ICS,6]
	IPCR	C08F0002-46 [I,C*]; C08F0002-48 [I,A]; C08K0005-00 [I,C*]; C08K0005-3492 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]; H01L0021-02 [I,C*]; H01L0021-02 [I,A]; H01L0021-30 [I,A]
	ECLA	C08K005/3492+L61/06; G03F007/004D; G03F007/029A

OS MARPAT 123:156423
GI



I

AB The title composition comprises a photosensitive s-triazine compound, a novolak resin, an acid splittable compound and propylene glycol monoalkyl ether and/or its ester where the s-triazine compound is selected from I [R1, R2 = haloalkyl, haloalkenyl; R3 = H, Me; R4 = aryl, heterocyclyl; n = 1, 2; Z =

bond, p-phenylene]. The material has improved solubility and sensitivity and
is almost free from any error.
ST photoresist compn neg triazine compd
IT Resists
(photo-, neg.-type; s-triazine photosensitive compound)
IT 42573-57-9 42880-03-5 42880-04-6 42880-05-7 42880-06-8
42880-07-9 42880-08-0 42880-09-1 42880-10-4 97802-67-0
97802-70-5 97802-71-6 97802-72-7 97802-73-8 97802-84-1
129509-22-4 151052-44-7 154880-05-4 155050-58-1 156360-76-8
166891-14-1 166891-15-2 166891-16-3 166891-17-4 166891-18-5
166891-19-6 166891-20-9 166891-21-0 166891-22-1 166891-23-2
166891-24-3 166891-25-4 166891-26-5 166891-27-6 166891-28-7
166891-29-8 166891-30-1 166891-31-2 166891-32-3 166891-33-4
166891-34-5 166891-35-6
RL: MOA (Modifier or additive use); USES (Uses)
(photosensitive compound)
OSC.G 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD (1 CITINGS)
UPOS.G Date last citing reference entered STN: 16 Feb 2009
OS.G CAPLUS 2002:253086

L6 ANSWER 15 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 1995:717175 CAPLUS <<LOGINID::20100303>>
DN 123:213224
OREF 123:37717a,37720a
ED Entered STN: 03 Aug 1995
TI Negative-working radiation-sensitive resist compositions containing bis(trichloromethyl)triazines
IN Kobayashi, Masaichi; Yamazaki, Hiroyuki; Harada, Yoichiro; Tanaka, Hatsuyuki; Nakayama, Toshimasa
PA Tokyo Ohka Kogyo Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-038
ICS G03F007-004; G03F007-029; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

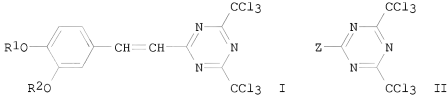
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 07134412	A	19950523	JP 1993-282824	19931111
PRAI JP 1993-282824		19931111		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07134412	ICM	G03F007-038
	ICS	G03F007-004; G03F007-029; H01L021-027
	IPCI	G03F0007-038 [ICM,6]; G03F0007-004 [ICS,6]; G03F0007-029 [ICS,6]; H01L0021-027 [ICS,6]; H01L0021-02 [ICS,6,C*]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029

[I,C*]; G03F0007-029 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]

GI



AB The resist compns. contain: (A) an alkali soluble resin and an alkkoymethylated amino resin and (B) triazine derivs. I (R1-2 = C1-3 alkyl) or I and triazines II [Z = 4-alkoxyphenyl, 4-alkoxynaphthyl, 2-(3,5-dialkoxyphenyl)ethenyl, 2-(2-furyl)ethenyl, 2-(5-alkyl-2-furyl)ethenyl, 3,4-methylenedioxyphenyl, 2-(3,4-methylenedioxyphenyl)ethenyl]. The compns. show a high sensitivity and high resolution and provide resist patterns with good profile.

ST neg working radiation sensitive resist; triazine photoacid generator radiation resist

IT Aminoplasts
RL: TEM (Technical or engineered material use); USES (Uses)
(neg.-working radiation-sensitive resist compns. containing (dialkoxystyryl)bis(trichloromethyl)triazines as photoacid generators)

IT Phenolic resins, preparation
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(novolak, cresol-based, neg.-working radiation-sensitive resist compns. containing (dialkoxystyryl)bis(trichloromethyl)triazines as photoacid generators)

IT Resists
(radiation-sensitive, neg.-working, neg.-working radiation-sensitive resist compns. containing (dialkoxystyryl)bis(trichloromethyl)triazines as photoacid generators)

IT 3584-23-4, 2-(4-Methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 42880-07-9 156360-76-8 160818-06-4
RL: TEM (Technical or engineered material use); USES (Uses)
(neg.-working radiation-sensitive resist compns. containing (dialkoxystyryl)bis(trichloromethyl)triazines as photoacid generators)

OSC.G 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD (1 CITINGS)
UPOS.G Date last citing reference entered STN: 16 Feb 2009
OS.G CAPLUS 2005:525068

L6 ANSWER 16 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 1977:163627 CAPLUS <<LOGINID::20100303>>
DN 86:163627
OREF 86:25625a,25628a
ED Entered STN: 12 May 1984
TI Chromophore-containing vinylhalomethyl-s-triazine photoinitiator
IN Bonham, James A.; Petrellis, Panayotis C.
PA Minnesota Mining and Manufacturing Co., USA
SO U.S., 8 pp.
CODEN: USXXAM
DT Patent
LA English
IC C07D251-24
INCL 260240000D
CC 74-4 (Radiation Chemistry, Photochemistry, and Photographic Processes)
FAN.CNT 3

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3987037	A	19761019	US 1971-177851	19710903
	NL 7211076	A	19730306	NL 1972-11076	19720814
	NL 172155	B	19830216		
	NL 172155	C	19830718		
	CA 986512	A1	19760330	CA 1972-150598	19720830
	GB 1388492	A	19750326	GB 1972-40496	19720831
	BE 788295	A1	19730301	BE 1972-121588	19720901
	DE 2243621	A1	19730308	DE 1972-2243621	19720901
	DE 2243621	C2	19870820		
	FR 2152039	A5	19730420	FR 1972-31062	19720901
	BR 7206066	D0	19730724	BR 1972-6066	19720901
	CH 576967	A5	19760630	CH 1972-12932	19720901
	JP 48036281	A	19730528	JP 1972-88304	19720902
	JP 59001281	B	19840111		
	IT 965195	B	19740131	IT 1972-52521	19720902
	US 3954475	A	19760504	US 1973-395419	19730910
	JP 56085746	A	19810713	JP 1980-144243	19801015
	JP 57001819	B	19820113		

PRAI US 1971-177851 A 19710903
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 3987037	IC	C07D251-24
	INCL	260240000D
	IPCI	C07D0251-24 [ICM]; C07D0251-00 [ICM,C*]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	NCL	544/216.000; 101/453.000; 430/281.100; 430/343.000;

		430/920.000; 522/063.000; 522/109.000; 522/121.000; 544/194.000; 544/211.000; 544/212.000; 544/219.000
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
NL 7211076	IPCI	C07D0055-12 [ICM]; C07D0057-00 [ICS]; G03C0001-68 [ICS]; G03C0001-72 [ICS]; C08F0001-16 [ICS]; C07D0099-02 [ICS]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
CA 986512	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
GB 1388492	IPCI	C09B0023-00 [ICM]; C09B0023-06 [ICS]; C09B0023-10 [ICS]; C09B0023-14 [ICS]; G03C0001-72 [ICS]; C08F0002-50 [ICS]; C08F0002-46 [ICS,C*]; G03C0001-68 [ICS]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
BE 788295	IPCI	C07D [ICM]
DE 2243621	IPCI	C07D0055-12 [ICM]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50

		[I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
FR 2152039	IPCI	C07D0055-00 [ICM]; C07D0099-00 [ICS]; C08F0029-00 [ICS]; G03C0007-00 [ICS]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
BR 7206066 [ICS]	IPCI	C08G0049-00 [ICM]; G03C0001-70 [ICS]; G03C0001-78
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
CH 576967	IPCI	C07D0251-22 [ICM]; C07D0251-24 [ICS]; C07D0251-00 [ICS,C*]; C08F0004-00 [ICS]; C08F0002-48 [ICS]; C08F0002-46 [ICS,C*]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
JP 48036281	IPCI	C07D0055-12
	IPCR	C08F0002-46 [I,A]; C08F0002-46 [I,C*]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,A]; G03C0001-675 [I,C*]; G03F0007-029 [I,A]; G03F0007-029 [I,C*]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14;

		C09B023/14H; G03C001/675; G03F007/029A
IT 965195	IPCI	B01J [ICM]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
US 3954475	IPCI	G03C0001-76 [ICM]; G03C0001-94 [ICS]; G03C0001-68 [ICS]; G03C0001-00 [ICS]
	IPCR	C08F0002-46 [I,C*]; C08F0002-46 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	NCL	430/281.100; 430/916.000; 430/920.000; 430/922.000; 522/063.000; 544/176.000; 544/386.000; 546/226.000
	ECLA	C08F002/46+IDT; G03C001/675; G03F007/029A
JP 56085746	IPCI	G03C0001-68 [ICM]; G03C0001-727 [ICS]; G03F0007-02 [ICS]; G03F0007-10 [ICS]; C08F0002-48 [ICA]; C08F0002-46 [ICA,C*]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A

AB A chromophore-containing vinylhalomethyl-s-triazine capable of generating a free radical upon irradiation to near UV or visible light (330-700 mμ) is used as a photoinitiator in free-radical photoimaging compns. Thus, a solution prepared from a poly(vinyl butyral) (Butavar B-72A, Monsanto Co.) 5, trimethylol propane trimethacrylate 3, 2,4-bis(trichloromethyl)-6-p-methoxystyryl-s-triazine 0.02 and dichloroethylene 100 parts was coated as a 2-mil layer on a polyester film, dried, laminated to another polyester film, exposed for 10 s to a I-W lamp through a photog. step wedge, the films were peeled apart and dusted with a toner powder to produce a pos. image corresponding to 4 steps on the wedge.

ST chromophore contg vinylhalomethyltriazine photoinitiator; triazine vinylhalomethyl photoinitiator photopolymer imaging

IT Vinyl acetal polymers

RL: USES (Uses)
(butyrals, photopolymerizable compns. containing chromophore-containing vinylhalomethyltriazine photoinitiator and, for photoimaging process)
IT Vinyl acetal polymers
RL: USES (Uses)
(formals, photopolymerizable compns. containing chromophore-containing vinylhalomethyltriazine photoinitiator and, for photoimaging process)
IT Photoimaging compositions and processes
(free-radical, photosensitive polymeric compns. containing chromophore-containing vinylhalomethyltriazine photoinitiators as)
IT 62579-98-0
RL: USES (Uses)
(color former, for photoimaging composition containing bis(trichloromethyl)methoxystyryltriazine photoinitiator, for magenta color image production)
IT 42573-57-9 42880-03-5 42880-04-6 42880-05-7 42880-07-9
42880-08-0 42880-09-1 42880-10-4 42880-11-5 42880-12-6
42880-13-7 42880-14-8 42880-15-9
RL: USES (Uses)
(photoinitiator, for free-radical photosensitive compns. for photog. image production)
IT 25085-82-9 35838-12-1
RL: USES (Uses)
(photopolymerizable compns. containing chromophore-containing vinylhalomethyltriazine photoinitiator and, for photog. image formation)
OSC.G 21 THERE ARE 21 CAPLUS RECORDS THAT CITE THIS RECORD (21 CITINGS)
UPOS.G Date last citing reference entered STN: 24 Feb 2010
OS.G CAPLUS 2008:1455183; 2005:1175707; 2006:185151; 1992:663027; 2007:376490; 2006:605131; 2004:293287; 2004:293280; 2004:293278; 2003:852844; 2003:796171; 2003:796061; 1999:635413; 1998:667955; 1997:805554; 1995:958474; 1986:226679; 1985:15163; 1984:456250; 1984:69316; 1983:613811

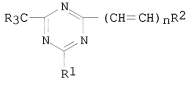
L6 ANSWER 17 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN
AN 1977:36343 CAPLUS <<LOGINID::20100303>>
DN 86:36343
OREF 86:5725a,5728a
ED Entered STN: 12 May 1984
TI Photosensitive elements containing chromophore-substituted vinyl-halomethyl-s-triazines
IN Bonham, James A.; Petrellis, Panayotis C.
PA Minnesota Mining and Manufacturing Co., USA
SO U.S., 9 pp.
CODEN: USXXAM
DT Patent
LA English
IC G03C001-76
INCL 096067000
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic Processes)
FAN.CNT 3

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

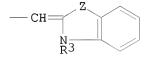
PI US 3954475 A 19760504 US 1973-395419 19730910
US 3987037 A 19761019 US 1971-177851 19710903
PRAI US 1971-177851 A3 19710903
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 3954475	IC	G03C001-76
	INCL	096067000
	IPCI	G03C0001-76 [ICM]; G03C0001-94 [ICS]; G03C0001-68 [ICS]; G03C0001-00 [ICS]
	IPCR	C08F0002-46 [I,C*]; C08F0002-46 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	NCL	430/281.100; 430/916.000; 430/920.000; 430/922.000; 522/063.000; 544/176.000; 544/386.000; 546/226.000
	ECLA	C08F002/46+IDT; G03C001/675; G03F007/029A
US 3987037	IPCI	C07D0251-24 [ICM]; C07D0251-00 [ICM,C*]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	NCL	544/216.000; 101/453.000; 430/281.100; 430/343.000; 430/920.000; 522/063.000; 522/109.000; 522/121.000; 544/194.000; 544/211.000; 544/212.000; 544/219.000
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A

GI



I



II

AB A chromophore-substituted (halomethyl) vinyl s-triazine derivative I (R = Br, Cl; R1 = CR3, NH2, NHR4, NR42, OR4 where R4 = Ph, alkyl; R2 = substituted aromatic, heterocyclic group, II where R3 = H, lower alkyl, Ph and Z = O, S;n = 1-3) generates free radicals upon irradiation with actinic radiation (330-700 nm) and is used as a photoinitiator for a photopolymerizable

composition for printing plates, relief photog. images and photoresists. Thus,
a photopolymerizable composition composed of a poly(vinylformal) (Formvar 15-95S, Monsanto Co.) 7.38, maleic anhydride-vinyl anhydride-vinyl acetate-vinyl chloride polymer 2.46, trimethylolpropane trimethacrylate 6,
tris(hydroxyethyl)isocyanurate trimethacrylate 2, Cyan XR-553758 (a phthalocyanine pigment from American Cyanamid) 1.22 and
2,4-bis(trichloromethyl)-6-p-methoxystyryl-s-triazine 0.4 was coated on an
anodized Al plate at 200 mg/ft2, dried at 140° F for 2 min, exposed through a step wedge to a C arc, and developed by treating with a solution
containing PrOH 35, H2O 62, (NH4)2SO3 1.5 and (NH4)H2PO4 1.5% and rubbing with
a pad to remove the nonexposed areas to give 11 steps vs. 1 step for a control using benzoin methyl ether as the photoinitiator.

ST photopolymerizable compn halomethylvinyltriazine initiator; image relief photog photopolymerizable compn

IT Vinyl acetal polymers
RL: USES (Uses)
(formals, photopolymerizable compns. containing, for photog. images and
printing plates)

IT Printing plates
(photopolymerizable compns. for, containing (halomethyl)vinyltriazine photoinitiators)

IT Photoimaging compositions and processes
(photopolymerzable compns. containing (halomethyl)vinyl triazine photoinitiators for)

IT Resists
(photo-, photopolymerizable compns. containing (halomethyl)vinyl triazine
photoinitiators for)

IT 42573-57-9
RL: USES (Uses)
(photopolymerizable composition containing, for printing plates and photoresists)

IT 3290-92-4 9003-22-9 35838-12-1
RL: USES (Uses)
(photopolymerizable compns. containing (halomethyl)vinyltriazine photoinitiator and, for photog. images and printing plates)

IT 42880-03-5P 42880-04-6P 42880-05-7P 42880-07-9P
42880-08-0P 42880-09-1P 42880-11-5P 42880-12-6P 42880-13-7P
42880-14-8P 42880-15-9P 61413-27-2P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation of)

OSC.G 15 THERE ARE 15 CAPLUS RECORDS THAT CITE THIS RECORD (15 CITINGS)

UPOS.G Date last citing reference entered STN: 12 Mar 2009

OS.G CAPLUS 1992:663027; 2004:293287; 2004:293280; 2004:293278; 2003:696378; 2003:1277; 1999:90242; 1995:958474; 1993:678838; 1989:125483; 1986:99530; 1985:15163; 1983:613811; 1982:627544; 1982:190687

L6 ANSWER 18 OF 18 CAPLUS COPYRIGHT 2010 ACS on STN

AN 1973:516093 CAPLUS <<LOGINID::20100303>>
DN 79:116093
OREF 79:18859a,18862a
ED Entered STN: 12 May 1984
TI Chromophore-substituted vinylhalomethyl-s-triazine
IN Bonham, James A.; Petrellis, Panayotis C.
PA Minnesota Mining and Manufacturing Co.
SO Ger. Offen., 23 pp.
CODEN: GWXXBX
DT Patent
LA German
IC C07D; G03C
CC 36-6 (Plastics Manufacture and Processing)
Section cross-reference(s): 28, 74
FAN.CNT 3

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2243621	A1	19730308	DE 1972-2243621	19720901
	DE 2243621	C2	19870820		
	US 3987037	A	19761019	US 1971-177851	19710903
PRAI	US 1971-177851	A	19710903		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 2243621	IC	C07D; G03C
	IPCI	C07D0055-12 [ICM]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A
US 3987037	IPCI	C07D0251-24 [ICM]; C07D0251-00 [ICM,C*]
	IPCR	C07D0251-22 [I,A]; C07D0251-00 [I,C*]; C07D0251-24 [I,A]; C07D0403-00 [I,C*]; C07D0403-06 [I,A]; C07D0413-00 [I,C*]; C07D0413-06 [I,A]; C08F0002-00 [I,C*]; C08F0002-00 [I,A]; C08F0002-46 [I,C*]; C08F0002-46 [I,A]; C08F0002-48 [I,A]; C08F0002-50 [I,A]; C09B0023-00 [I,C*]; C09B0023-01 [I,A]; C09B0023-06 [I,A]; C09B0023-14 [I,A]; G03C0001-675 [I,C*]; G03C0001-675 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-029 [I,C*]; G03F0007-029 [I,A]
	NCL	544/216.000; 101/453.000; 430/281.100; 430/343.000; 430/920.000; 522/063.000; 522/109.000; 522/121.000; 544/194.000; 544/211.000; 544/212.000; 544/219.000
	ECLA	C08F002/46+IDT; C09B023/00S; C09B023/06; C09B023/14; C09B023/14H; G03C001/675; G03F007/029A

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AB A title compound (I) where R is Cl3C or H2N, R1 is Ph, substituted phenyl,
or a heterocyclic radical, and n is 1-3), useful as photoinitiators in the
manufacture of printing plates and light-sensitive elements for photo
duplication systems, were prepared by condensing the appropriate s-triazine
derivative with aldehydes or salts of aldehyde derivative Thus, a mixture of 330
parts 2,4-bis(trichloromethyl)-6-methyl-s-triazine [949-42-8] and 149.6
parts p-anisaldehyde [123-11-5] in 1 l. toluene containing 45 parts
piperidinium acetate was refluxed while distilling water to give
2,4-bis(trichloromethyl)-6-p-methoxystyryl-s-triazine (II) [42573-57-9].
The performance of a printing plate prepared by coating an anodized Al plate
with a resin composition containing II was superior to similar plates prepared with
resin composition containing conventional photo initiators.
ST chromophore contg triazine deriv; photoinitiator triazine deriv; photog
sensitizer triazine deriv; printing plate light sensitizer;
photoduplication light sensitizer
IT Photographic sensitizers
(chromaphore-containing triazine derivs.)
IT Printing plates
(light sensitizers for manufacture of, chromaphore-containing triazine derivs.
as)
IT Photoduplication
(light sensitizers for, chromaphore-containing triazine derivs.)
IT Light, chemical and physical effects
(sensitizers, chromaphore-containing triazine derivs.)
IT 42880-03-5 42880-04-6 42880-05-7 42880-06-8 42880-07-9
42880-08-0 42880-09-1 42880-10-4 42880-11-5 42880-12-6
42880-13-7 42880-14-8 42880-15-9
RL: USES (Uses)
(light sensitizers, for photoduplication and printing plate manufacture)
IT 949-42-8
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with aldehydes)
IT 123-11-5 6203-18-5 42880-17-1
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with triazine derivs.)

=> D HIS

(FILE 'HOME' ENTERED AT 15:55:01 ON 03 MAR 2010)

FILE 'REGISTRY' ENTERED AT 15:55:15 ON 03 MAR 2010
L1 246 S TRIAZINE AND ETHENYL AND TRICHLORO
L2 12 S L1 AND ETHOXY
L3 2 S L1 AND DIETHOXY
L4 24 S L1 AND DI AND OXY

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L5 1 S 42880-07-9

FILE 'CAPLUS' ENTERED AT 15:59:06 ON 03 MAR 2010
L6 18 S L5

=> LOG Y

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	63.32	163.78
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	-15.30	-15.30

STN INTERNATIONAL LOGOFF AT 15:59:34 ON 03 MAR 2010